



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION OF

Mitsuaki KOMINO et al.

Appln. No.: 09/667,770

Filed: September 22, 2000

Title: PLASMA PROCESSING APPARATUS, AND ELECTRODE STRUCTURE AND
TABLE STRUCTURE OF PROCESSING APPARATUS

Confirmation No.: 8174

Group Art Unit: 1763

Examiner: R. Zervigon

May 28, 2002

May 26=Sunday; May 27=Holiday

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AMENDMENT

Hon. Commissioner of Patents
Washington, D.C. 20231

Sir:

In response to the Office Action dated December 26, 2001, please amend the above
identified application as follows:

IN THE CLAIMS:

Kindly cancel claims 1, 5, 6, 8, 9, 10, 16-20, ~~22~~⁷, 26 and 28 without prejudice.

Kindly enter the following amended claims:

2. (Amended) An electrode structure used in a plasma processing apparatus which
performs a predetermined process on an object to be processed by using a plasma in a process
chamber in which a vacuum can be formed, the electrode structure comprising:

an electrode unit having a heater unit therein;

a cooling block joined to the electrode unit and having a cooling jacket which cools
said electrode unit;

a labyrinth heat transfer space formed by a concentric or spiral groove provided on at
least one of opposite surfaces of said electrode unit and said cooling block; and

electrode-side heat transfer gas supply means for supplying a heat transfer gas to said
labyrinth heat transfer space.

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